

Title (en)
High-performance ion source and method for generating an ion beam

Title (de)
Hochleistungs-Ionenquelle und Verfahren zum Erzeugen eines Ionenstrahls

Title (fr)
Source d'ions à haute performance et procédé de génération d'un faisceau d'ions

Publication
EP 2669929 A1 20131204 (EN)

Application
EP 12169819 A 20120529

Priority
EP 12169819 A 20120529

Abstract (en)
An ion source, in which a divergent skimmer electrode is placed, spatially separated from, but in short spatial distance downstream from the tip of the tip electrode, and in which a sheath gas is supplied to flush around the tip electrode, allows achieving a stable and high-flux ion beam. The dimensions of the skimmer electrode may be chosen to adjust the pressure difference across the skimmer electrode, and may support the formation of two Mach cones. This combination of features allows to greatly enhance the ion current, a significant improvement for deposition applications in particular.

IPC 8 full level
H01J 49/16 (2006.01); **H01L 21/02** (2006.01)

CPC (source: EP)
H01J 49/165 (2013.01)

Citation (applicant)

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Citation (search report)

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Designated contracting state (EPC)
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)
BA ME

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